EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2	"20060257667"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/03 17:04
S2	44	silicon-aluminum adj2 (film or layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 08:54
S3	9776	USR.as.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 10:26
S4	142	Yokoyama-Yasuaki.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 10:27
S5	282	Matsuki-Yasuo.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 10:27

S6	118	(S4 or S5) and (silicon or si or silane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 10:40
S7	108	(S4 or S5) and (silicon or si or silane) and (coat$4 or film)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 10:41
S8	99	(S4 or S5) and (silicon or si or silane) same (coat$4 or film or layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 10:41
S9	205	((S3 or S4 or S5) not S8) and (silicon or si or silane) adj2 (aluminum or al or aluminium)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 11:22
S10	65	((S3 or S4 or S5) not S8) and ((silicon or si or silane) adj2 (aluminum or al or aluminium)) same (coat$4 or layer or film or deposit$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 11:23
S11	204	(S3 or S4 or S5) and (aluminum or aluminium) near3 (coat$4 or film or layer or deposit$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 11:29

S12	184	(S3 or S4 or S5) and (aluminum or aluminium) near3 (coat$4 or film or layer or deposit$4) and (heat or light or ultraviolet or laser)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 11:30
S13	173	((S3 or S4 or S5) and (aluminum or aluminium) near3 (coat$4 or film or layer or deposit$4) and (heat or light or ultraviolet or laser)) not S8	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 11:31
S14	773	423/348,349.ccls. and (silicon or si or silane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:22
S15	465	423/348,349.ccls. and (silicon or si or silane) and (aluminum or aluminium or al)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:23
S16	361	423/348,349.ccls. and (silicon or si or silane) same (aluminum or aluminium or al)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:23
S17	286	423/348,349.ccls. and (silicon or si or silane) same (aluminum or aluminium or al) and (coat$4 or film or layer or deposit$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:23

S18	61	423/348,349.ccls. and (silicon or si or silane) near10 (liquid or solution) same (aluminum or aluminium or al) and (coat$4 or film or layer or deposit$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:24
S19	142	Yokoyama-Yasuaki.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:28
S20	282	Matsuki-Yasuo.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:28
S21	99	(S19 or S20) and (silicon or si or silane) same (coat$4 or film or layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:28
S22	9776	JSR.as.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:28
S23	173	((S22 or S19 or S20) and (aluminum or aluminium) near3 (coat$4 or film or layer or deposit$4) and (heat or light or ultraviolet or laser)) not S21	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:28

S24	333	S21 or S23 or S18	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:30
S25	43792	(aluminum or aluminium or al) adj2 (silicon or si) same (coat$4 or layer or film or deposit)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:32
S26	98	423/324-350.ccls. not S24 and S25	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:33
S27	431	S26 or S24	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:46
S28	11874	427/344,372.2,383.3,383.7,384,387,388.1,397.7.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:47
S29	251	427/344,372.2,383.3,383.7,384,387,388.1,397.7.ccls. and S25	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:47

S30	46803	(aluminum or aluminium or al) adj2 (silicon or si) same (coat$4 or layer or film or deposit or metalli$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 13:48
S31	680	S29 or S27	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:10
S32	39220	("427".clas. not S31) and (aluminum or aluminium or al or Group adj2 III$1) and (silicon or si or silane or Group adj2 IV$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:12
S33	21049	("427".clas. not S31) and (aluminum or aluminium or al or Group adj2 III$1) same (silicon or si or silane or Group adj2 IV$1) and (coat$4 or layer or thin or deposit$ or metalli$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:13
S34	8375	C23C018/$5.ipc.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:14
S35	10829	C22C021/$4.ipc.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:15

S36	580	C03C17/$5.ipc.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:15
S37	10829	C22C021/$5.ipc.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:15
S38	6196	H01B005/$5.ipc.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:15
S39	73522	H01L031/$5.ipc.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:18
S40	99081	S34 or S35 or S36 or S37 or S38 or S39	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:23
S41	99051	S40 not S31	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:24

S42	1590	S41 and S30	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:24
S43	89	S41 and S30 and (heat$4 or light or ultraviolet or ultra-violet or thermal$5) near (decompos$6 or cure or cured or curing or dry or drying)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:26
S44	769	S43 or S31	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 14:44
S45	86	L03-E05B$1 and (M13-B$2 or U11-C05C6$2 or U11-C05C7$2)	DERWENT	ADJ	ON	2008/03/04 14:46
S46	855	S45 or S43 or S31	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 15:09
S47	1927	252/62.3$1.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 15:09
S48	16907	252/500-521.6.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 15:09

S49	1597	((S47 or S48) not S46) and (heat$4 or light or ultraviolet or ultra-violet or thermal$5) near (decompos$6 or cure or cured or curing or dry or drying)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 15:13
S50	197	((S47 or S48) not S46) and (heat$4 or light or ultraviolet or ultra-violet or thermal$5) near (decompos$6 or cure or cured or curing or dry or drying) and (aluminum or aluminium or al) near5 (silicon or si)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 15:14
S51	189	((S47 or S48) not S46) and (heat$4 or light or ultraviolet or ultra-violet or thermal$5) near (decompos$6 or cure or cured or curing or dry or drying) and (aluminum or aluminium or al) near5 (silicon or si) and (coat$4 or film or layer or deposit$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 15:15
S52	1044	S51 or S46	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 15:18
S53	346	(("427".clas. or "252".clas.) not S52) and (aluminum or aluminium) adj2 hydride and (heat$4 or thermal$5 or light or ultraviolet or ultra-violet) near10 (cure or cured or curing or decompos$6 or dry or drying or metalli$6)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 15:22
S54	183	S53 and (silicon or si)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/04 15:24
S55	3	(5793479|4599277|58611879|5882722).pn.	USPAT	ADJ	ON	2008/03/04 15:24

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